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# United States Patent [19]

Forrest et al.

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[54] **METHOD FOR DEPOSITION AND PATTERNING OF ORGANIC THIN FILM**

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[57] **ABSTRACT**

A patterning system with a photoresist overhang allows material to be deposited onto a substrate in various positions by varying the angle from which the material is deposited, and by rotating the substrate. The patterning system can be used to fabricate a stack of organic light emitting devices on a substrate using the same patterning system and without removing the substrate from vacuum.

**12 Claims, 14 Drawing Sheets**

